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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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09/910,073

APPLICANT
Hans Martin HERTZ *et al.*

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July 23, 2001

GROUP
2882

U.S. PATENT DOCUMENTS

Examiner Initials	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication (MM-DD-YYYY)
	Number	Kind Code (if known)		
J.Y.	6,069,937		Oshino <i>et al.</i>	05/2000
J.Y.	6,011,267		Kubiak <i>et al.</i>	01/2000
J.Y.	6,002,744		Hertz <i>et al.</i>	12/1999
J.Y.	5,577,092		Kubiak <i>et al.</i>	11/1996
J.Y.	4,953,191		Smither <i>et al.</i>	08/1990

FOREIGN PATENT DOCUMENTS

Examiner Initials	Foreign Patent Document		Country	Date of Publication (MM-DD-YYYY)	Translation	
	Number	Kind Code (if known)			Yes	no
J.Y.	0 186 491	A2	EPC	07/1986		
J.Y.	WO 99/34395	A1	PCT	07/1999		
J.Y.	WO 97/40650	A1	PCT	10/1997		
J.Y.	5-258692		Japan	10/1993	x	

NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Include name of author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
J.Y.	Ter-avertisyan et Al. "Soft X-ray Emission of E-beam Excited Clustered Supersonic Gas Jet" <i>Institute of Physical Research of the National Armenian Academy of Sciences</i> (Ashtarak-2, 378410, Armenia)
J.Y.	Malmqvist <i>et al.</i> "Liquid-jet Target For Laser-plasma Soft X-ray Generation" <i>American Institute of Physics</i> , (Sept. 1996) pp. 4150-4153
J.Y.	Kubiak <i>et al.</i> "Debris-Free EUVL Sources Based on Gas Jets" <i>Optical Society of America, OSA On Extreme Ultraviolet Lithograph</i> , 1996 Vol. 4,
Examiner Signature	<i>Marie Yun</i>
Date Considered	6-03

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